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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/844,991	04/27/2001		Maurice Rivoire	AMAT/5297/DD/LOW K/JW	1361	
32588	7590	03/24/2004		EXAMINER		
APPLIED 2881 SCOT		ALS, INC.	ROSE, ROBERT A			
SANTA CL				ART UNIT PAPER NUMBER		
	,			3723		
				DATE MAILED: 03/24/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)					
		09/844,991	RIVOIRE ET AL.	\mathcal{O}^{N}				
	Office Action Summary	Examiner	Art Unit					
		Robert Rose	3723					
Period fo	The MAILING DATE of this communication app r Reply	ears on the cover sheet with the c	rrespondence address -					
THE I - Exter after - If the - If NO - Failui Any r	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Issions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, eply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communica D (35 U.S.C. § 133).	ation.				
Status								
1) 🛛	Responsive to communication(s) filed on 22 De	ecember 2003.						
		action is non-final.						
3)[) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.							
Dispositi	on of Claims	,						
4)⊠ 5)□ 6)⊠ 7)□	Claim(s) 8,10-19,21,24-30 and 32-36 is/are per 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) 8,10-19,21,24-30 and 32-36 is/are rejected to. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or	vn from consideration.						
Application	on Papers							
10) 🔲 -	The specification is objected to by the Examiner The drawing(s) filed on is/are: a) acce Applicant may not request that any objection to the of Replacement drawing sheet(s) including the correcti The oath or declaration is objected to by the Ex-	epted or b) objected to by the Edrawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.12					
Priority u	nder 35 U.S.C. § 119							
12)[/ a)[Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau ee the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stage					
Attachment	(s)							
	e of References Cited (PTO-892)	4) Interview Summary						
3) 🛛 Inform	e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) No(s)/Mail Date 13.	Paper No(s)/Mail Da 5) Notice of Informal Pa 6) Other:	ite atent Application (PTO-152)					

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DETAILED ACTION

- 1. Receipt is acknowledged of Applicant's Prior art Statement, filed December 22, 2003.
- 2. Claims 1-7, 9, 20, 22-23, and 31 have been canceled.
- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 8, 10-19, 21, 24-30, and 32-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Homma et al in view of WO 00/49647. Homma et al disclose a method for polishing organosilicate layer on a substrate comprising substantially all of the subject matter set forth in Applicant's claims above. Note the use of an aqueous solution of abrasive within the pH range recited. The values of pressure and platen rotational speed disclosed in Homma et al are within the recited ranges of polishing pressure and platen rotational speed. While Homma et al disclose ceria as the abrasive of choice, it is known from WO 00/49647 to use silicon dioxide colloidal or fumed slurry in lieu of ceria, to polish layers on wafers(page 11, lines 19-21). To substitute a conventional inexpensive abrasive such as silicon dioxide, aluminum oxide, zirconium oxide, or titanium oxide for the ceria abrasive in the method of Homma et al would have been obvious in view of WO 00/49647. The recited percent weight of the abrasive slurry recited falls within the range set forth in WO 00/49647(page 6, lines 21-22), and to perform the method of Homma et al with abrasive concentration within this range would have been obvious in view of WO 00/49647.



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5. Applicant's arguments filed December 22, 2003 have been fully considered but they are not persuasive. Applicant has argued that the primary reference to Homma et al, while disclosing the polishing of an organic insulating film on a wafer, teaches only the use of ceria as a suitable abrasive in the slurry.

Homma et al defines an "organic insulating film" at column 3, lines 55-60 as being comprised predominately of silicon, with 1% or more of organic components. This film is precisely the organosilicate film to which Applicants invention is directed. In the improvement of Homma et al, purified ceria was found to be superior to unpurified ceria in lowering the degree of contamination. While the disclosure of Homma et al is directed to an improved method of polishing this film utilizing purified ceria abrasive, the improvement is over a more common prior art polishing process also disclosed in Homma et al(at column 6, line 35), which in the past has utilized conventional silica slurry to polish such films. WO 00/49647 was merely cited in the rejection to show the known interchangeability and alternative use of conventional metal oxide abrasives such as silicon dioxide, ceria, and various other metal oxides in polishing wafers. The conventional use of KOH with silicon dioxide slurry is taught by the prior art method mentioned in Homma et al(column 1, lines 25-31).

6. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period

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will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

7. Any inquiry concerning this communication should be directed to Robert Rose at telephone number (703) 308-1360.

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March 17, 2004.

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